

Abstract

Provided is a polishing pad which is capable of providing a high flatness to a polishing workpiece and
5 suppressing the formation of scratches, and a method therefor. The polishing pad comprises a foamed urethane sheet on the surface which includes closed cells and open cells and which satisfies the following requirements: (1) an open cell ratio is 20-80 vol% where the total volume of
10 closed cells and open cells is taken as 100 vol%, (2) the ratio $[\tan\delta(\text{wet/dry})\text{ratio}]$ of a loss factor $\tan\delta$ in a water-absorption state to that in a dry state is 1.3-1.7, the loss factors being measured according to JIS K7244-4 with an initial load of 20 g at a measuring frequency of 1
15 Hz at a temperature of 26°C in a tensile mode over a strain range from 0.01 to 0.1%, and (3) the Shore D0 hardness according to ASTM D2240 is 60-80.